



PATENT
2224-163P

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IN THE U.S. PATENT AND TRADEMARK OFFICE

Applicant: Tatsuya NAKANO

International

Appl. No.: PCT/JP99/02637

Group: Unassigned

Appln. No.: 09/463,059

Filed: January 19, 2000

Examiner: UNASSIGNED

For: ACID-SENSITIVE COMPOUND AND RESIN
COMPOSITION FOR PHOTORESIST

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TC 1700 MAIL ROOM

LETTER SUBMITTING PAPER
BEARING ORIGINAL SIGNATURE

Assistant Commissioner for Patents
Washington, DC 20231

April 28, 2000

Sir:

In the above-identified application, a copy of the original executed Declaration and Power of Attorney was submitted to the U.S.P.T.O. on January 19, 2000.

As evidence of authenticity of the copy under 37 C.F.R. § 1.4(d)(2), Applicant submits herewith the original executed Declaration and Power of Attorney, and requests that it be made part of the Prosecution History of the above-identified application

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by being added to the contents of the file wrapper of the above-identified application.

If necessary, the Commissioner is hereby authorized in this, concurrent, and future replies, to charge payment or credit any overpayment to Deposit Account No. 02-2448 for any additional fee required under 37 C.F.R. §§ 1.16 or 1.17; particularly, extension of time fees.

Respectfully submitted,

BIRCH, STEWART, KOLASCH & BIRCH, LLP

By  #32,868

~~S/~~ Raymond C. Stewart, #21,066

RCS/EHV:jls
2224-163P

P.O. Box 747
Falls Church, VA 22040-0747
(703) 205-8000

Attachment

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